



Att'y. Dkt. No. AMAT/4213.P1/MASK/MASK-ETCH/ARNOLD S

RECEIVED
JAN 29 2004
TC 1700

www.pearsoned.com

Group Art Unit: 1765

Serial No.: 10/024,958

Confirmation No.: 3439

Filed: December 18, 2001

Examiner: Kin-Chan Chen

For: Etch Process Photolithographic Reticle Manufacturing with Improved Etch Bias

MAIL STOP Non-Fee Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

37 CFR 1.8

I hereby certify that this correspondence is being deposited on January 20, 2004, with the United States Postal Service as First Class Mail in an envelope addressed to: Mail Stop Non-Fee Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

01/10/2004
Date

B. H.
Signature

Dear Sir:

RESPONSE TO OFFICE ACTION DATED OCTOBER 20, 2003

In response to the Office Action dated October 20, 2003, having a shortened statutory period for response set to expire on January 20, 2004, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicant believes that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/4213.P1/BKH, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper. **Remarks/Arguments** begin on page 7 of this paper.